



PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Naomasa SHIRAISHI

Group Art Unit: 2851

Application No.: 09/690,591

Examiner: K. Brown

Filed: October 18, 2000

Docket No.: 107629

For: EXPOSURE METHOD AND APPARATUS, AND
METHOD OF FABRICATING A DEVICE

AMENDMENT

Director of the U.S. Patent and Trademark Office
Washington, D.C. 20231

Sir:

In reply to the October 4, 2002 Office Action, the shortened statutory period for reply being extended by the attached Petition for Extension of Time, please amend the above-identified application as follows:

IN THE CLAIMS:

Please cancel claims 1-3, 6-11 and 13-15 without prejudice to or disclaimer of the subject matter contained therein.

Please replace claims 4, 5 and 12 as follows:

4. (Amended) An exposure method in which a second object is exposed, via a projection system, with an exposure beam that has passed a pattern of a first object, said exposure method comprising:

disposing a stage holding said first object or said second object and moving on a base member in a space supplied with a first gas that transmits said exposure beam;

RECEIVED
APR - 9 2003
TECHNOLOGY CENTER 2800

RECEIVED
APR - 9 2003
TECHNOLOGY CENTER 2800

04/08/2003 HARDELR1 00000021 09690591
01 FC:1202
234.00 dp